

**WEST**

Generate Collection

Print

L1: Entry 1 of 2

File: EPAB

May 30, 1984

PUB-NO: DE003240643A1

DOCUMENT-IDENTIFIER: DE 3240643 A1

TITLE: Production of conductor track coatings and conductive hole wall coatings on or in circuit boards

PUBN-DATE: May 30, 1984

## INVENTOR-INFORMATION:

NAME

COUNTRY

TOLLS, ELMAR DR

DE

SCHNEIDER, EHRENHARD

DE

PLATZEN, ROLF

DE

## ASSIGNEE-INFORMATION:

NAME

COUNTRY

LPW CHEMIE GMBH

DE

APPL-NO: DE03240643

APPL-DATE: November 4, 1982

PRIORITY-DATA: DE03240643A (November 4, 1982)

US-CL-CURRENT: 205/164; 205/920

INT-CL (IPC): C25D 7/00; C25D 3/38

EUR-CL (EPC): C25D003/38

## ABSTRACT:

CHG DATE=19990617 STATUS=O> A copper bath, known in connection with the production of bright copper precipitates, of the composition 10-50 g/l of copper as +2-valent ions, 20-220 g/l of sulphuric acid and 1-200 mg/l of chloric acid is used for the electrolytic production of circuit board coatings and conductive hole wall coatings in circuit boards having holes. The copper bath additionally contains polyglycol and/or nonionic wetting agents and organic thio compounds having water-solubilising groups, but is free of planarisers. This is carried out at a temperature of more than 30 DEG C, preferably about 40 DEG C, and the current density is maintained in the range 5-15 A/dm<2>.

**WEST****End of Result Set**

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L1: Entry 2 of 2

File: DWPI

May 30, 1984

DERWENT-ACC-NO: 1984-140962

DERWENT-WEEK: 198423

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TITLE: Copper electroplating printed circuit board contg. through-holes - from bath contg. added polyglycol or nonionic wetting agent and organic thio cpd. operated at high temp. and current density

INVENTOR: PLATZE, R; SCHNEIDER, E ; TOLLS, E

PATENT-ASSIGNEE:

ASSIGNEE

CODE

LPW-CHEMIE GMBH

LPWCN

PRIORITY-DATA: 1982DE-3240643 (November 4, 1982)

PATENT-FAMILY:

PUB-NO

PUB-DATE

LANGUAGE

PAGES

MAIN-IPC

DE 3240643 A

May 30, 1984

008

DE 3240643 C

January 21, 1988

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APPLICATION-DATA:

PUB-NO

APPL-DATE

APPL-NO

DESCRIPTOR

DE 3240643A

November 4, 1982

1982DE-3240643

INT-CL (IPC): C25D 3/38; C25D 7/00

ABSTRACTED-PUB-NO: DE 3240643A

BASIC-ABSTRACT:

In using a standard bright Cu plating bath contg. 10-50 g/l cupric ions, 20-200 g/l H<sub>2</sub>SO<sub>4</sub> and 1-200 mg/l chloride ions for electroplating printed circuit boards contg. through-holes, the plating bath additionally comprises polyglycol or nonionic wetting agents and organic thio-cpds. contg. water-solubilising gps. but is free from levelling agents. Plating takes place above 30(40) deg.C and current density is kept at 5-15 A/sq.dm.

On increasing the temp. and average current density, plating time is reduced, e.g. to 20 min. for applying a 30  $\mu$ -thick layer. A good layer thickness distribution of hole wall to surface is achieved. The Cu layer has high ductility.

ABSTRACTED-PUB-NO:

DE 3240643C

EQUIVALENT-ABSTRACTS:

In the prodn. of conductor plates drilled with holes a smooth copper coating of the plates is achieved by using a copper bath free from levels and contg. 10-50 g/l Cu as divalent ions, 20-220 g/l sulphuric acid, 1-220 mg/l chloride ions, polyglycol or nonionic wetting agents and organic thio cpds. with gps. making them water soluble and working at temps. over 30(40) deg.C and with current density 5-15 A/dm<sup>2</sup>.

ADVANTAGE - Copper is deposited smoothly and layer has high ductility.

(3pp)

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: COPPER ELECTROPLATING PRINT CIRCUIT BOARD CONTAIN THROUGH HOLE BATH  
CONTAIN ADD POLYGLYCOL NONIONIC WET AGENT ORGANIC THIO COMPOUND OPERATE HIGH  
TEMPERATURE CURRENT DENSITY

DERWENT-CLASS: A97 L03 M11 V04

CPI-CODES: A05-H01; A12-E07A; A12-W12D; L03-H04E3; M11-A03;

EPI-CODES: V04-R02; V04-R05;

UNLINKED-DERWENT-REGISTRY-NUMBERS: 1714S; 1759S ; 5214U

POLYMER-MULTIPUNCH-CODES-AND-KEY-SERIALS:

Key Serials: 0011 0013 0213 0229 0231 1279 1282 1581 2214 2481 2498 2585 3258 2740 3315

Multipunch Codes: 014 028 03- 04- 147 226 308 309 331 336 441 466 471 50& 53& 575 583  
589 623 627 628 651 678 688 720 723

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C1984-059542

> s de3240643/pn  
L1 1 DE3240643/PN

=> d all

L1 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2003 ACS  
AN 1984:618590 CAPLUS  
DN 101:218590  
TI Conductive strip coatings and conductive perforation wall coatings on or  
in circuit boards  
IN Tolls, Elmar; Schneider, Ehrenhard; Platzen, Rolf  
PA LPW-Chemie G.m.b.H., Fed. Rep. Ger.  
SO Ger. Offen., 8 pp.  
CODEN: GWXXBX  
DT Patent  
LA German  
IC C25D007-00; C25D003-38  
CC 72-8 (Electrochemistry)  
Section cross-reference(s): 76

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3240643	A1	19840530	DE 1982-3240643	19821104 <--
	DE 3240643	C2	19880107		
PRAI	DE 1982-3240643		19821104		

AB A well-known Cu electroplating bath for the prodn. of bright Cu  
electroplates consists of Cu (as Cu<sup>2+</sup>) 10-50, H<sub>2</sub>SO<sub>4</sub> 20-220 g/L, and Cl<sup>-</sup>  
1-200 mg/L and is used for the manuf. of conductive strip coatings and  
conductive perforation wall coatings. The Cu electroplating bath addnl.  
contains polyglycol or nonionic wetting agent and org. sulfo compds. with  
groups rendering them water-sol., but is free of leveling agents. It is  
used at a temp. of >30.degree. (preferably 40.degree.), and the c.d. is  
maintained at 5-15 A/dm<sup>2</sup>. In an example, an epoxide conductive strip  
reinforced with glass fibers is drilled and is electroplated in a bath of  
the following compn.: Cu sulfate 80, H<sub>2</sub>SO<sub>4</sub> 200, polyglycol (av. mol. wt.  
12,000) 2 g/L, Cl<sup>-</sup> 50, and N,N-diethyldithiocarbamic acid  
(.omega.-sulfopropyl) ester Na salt 10 mg/L. At a temp. of 20.degree.,  
for 20 min at a c.d. of 7.5 A/dm<sup>2</sup>, a layer thickness ratio of penetration  
wall/surface of 0.75:1 was ascertained. If one carries out the  
electroplating at 40.degree. under otherwise equal conditions, then a  
layer thickness ratio of 0.92:1 is obtained.

ST copper electroplating printed circuit; perforation wall coating circuit  
board

IT Polyoxyalkylenes

RL: USES (Uses)

(in electroplating, of copper on conductive strips and perforation  
walls of circuit boards)

IT Electric circuits

(printed, boards, copper electroplating on)

IT 7440-50-8, uses and miscellaneous

RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(electroplating of, on conductive strip and perforation walls of  
circuit boards)

IT 16887-00-6, uses and miscellaneous

RL: USES (Uses)

(in copper electroplating on conductive strip and perforation walls of  
circuit boards)

IT 591-08-2D, reaction product with methylphenylthiourea and propane sultone

1120-71-4D, reaction product with acetylthiourea and methylphenylthiourea  
4104-75-0D, reaction product with acetylthiourea and propane sultone  
6142-42-3

RL: PRP (Properties)

(in electroplating, of copper on conductive strips and perforation  
walls of circuit boards)

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